

MOSFET Models

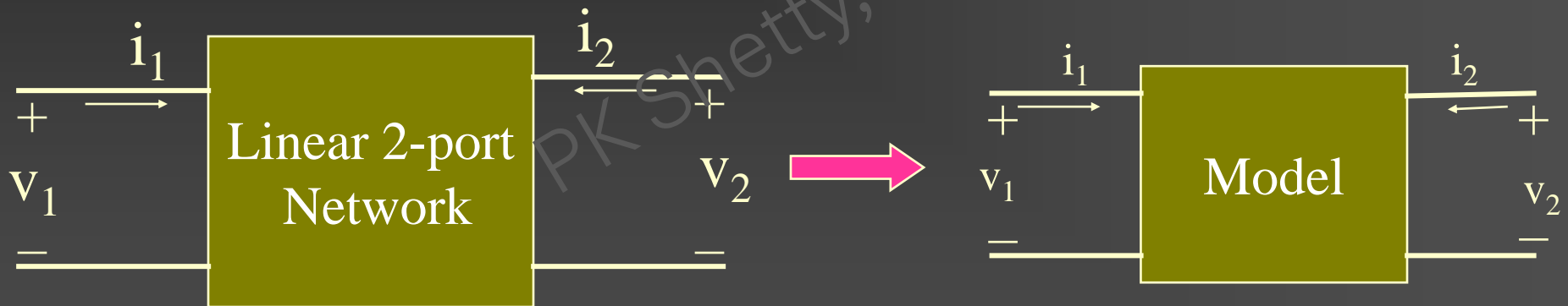
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Use of a Model

- Developing Design Equations
- Hand Analysis and Initial Computer Simulation

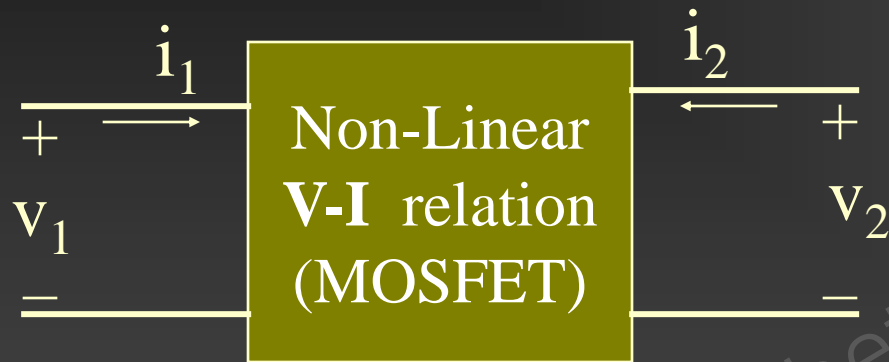
Model

We can have a model for any linear 2-port network.

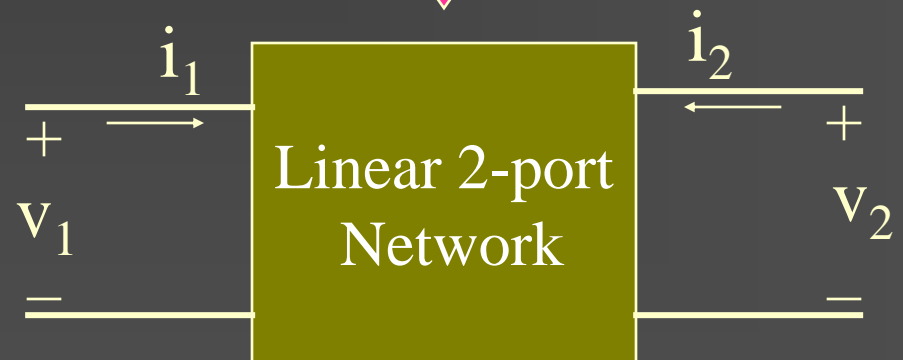
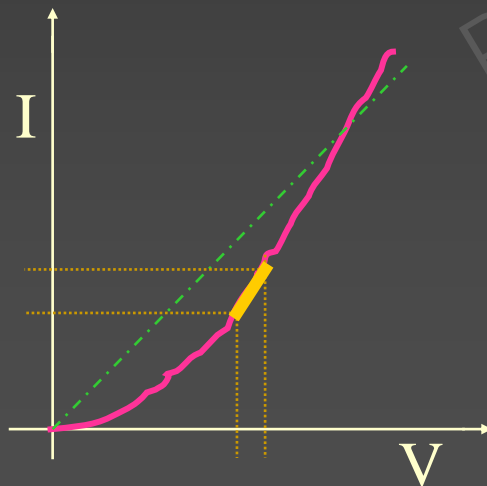


MOSFET Small Signal Model

Two Port Network:



For small signals

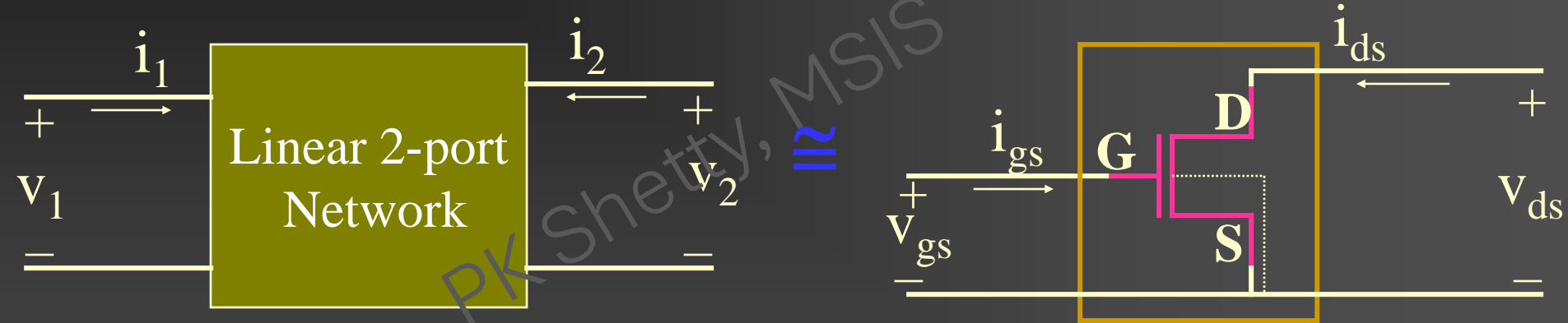


Various models

The electrical behavior of linear 2-port n/w can be modeled in terms of the following established sets of transfer function parameters:

- h - parameter model (hybrid)
- y - parameter model (admittance)
- g - parameter model (conductance)

MOSFET y-parameter model



$$\begin{aligned} i_1 &= y_{11}V_1 + y_{12}V_2 \\ i_2 &= y_{21}V_1 + y_{22}V_2 \end{aligned}$$

$$\begin{aligned} i_{gs} &= y_{11}V_{gs} + y_{12}V_{ds} \\ i_{ds} &= y_{21}V_{gs} + y_{22}V_{ds} \end{aligned}$$

MOSFET y-parameter model

$$\mathbf{i}_{gs} = y_{11}\mathbf{v}_{gs} + y_{12}\mathbf{v}_{ds} \quad \text{—————} (1)$$

$$\mathbf{i}_{ds} = y_{21}\mathbf{v}_{gs} + y_{22}\mathbf{v}_{ds} \quad \text{—————} (2)$$

For low frequencies, impedance between G and S is very high and hence $\mathbf{i}_{gs} \approx 0$.

\therefore from eqn. (1),

$$0 = y_{11}\mathbf{v}_{gs} + y_{12}\mathbf{v}_{ds}$$

i.e., input conductance, $y_{11} = \partial \mathbf{i}_{gs} / \partial \mathbf{v}_{gs} = 0$;

and, forward transconductance, $y_{12} = \partial \mathbf{i}_{gs} / \partial \mathbf{v}_{ds} = 0$;

MOSFET y-parameter model

$$\mathbf{i}_{ds} = y_{21} \mathbf{v}_{gs} + y_{22} \mathbf{v}_{ds} \quad (2)$$

For MOSFETs biased in saturation region,

$$I_{ds} = \frac{1}{2} KW/L (v_{gs} - v_t)^2 (1 + \lambda v_{ds}) \quad (3) \quad \text{where } K = \mu C_{ox}$$

From eqns. (2) and (3),

$$y_{21} = \partial \mathbf{i}_{ds} / \partial \mathbf{v}_{gs} = KW/L (v_{gs} - v_t) (1 + \lambda v_{ds}) ;$$

= reverse transconductance, \mathbf{g}_m .

$$y_{22} = \partial \mathbf{i}_{ds} / \partial \mathbf{v}_{ds} = \frac{1}{2} \lambda KW/L (v_{gs} - v_t)^2 ;$$

= output conductance, $\mathbf{g}_o \approx \lambda \mathbf{i}_{ds}$

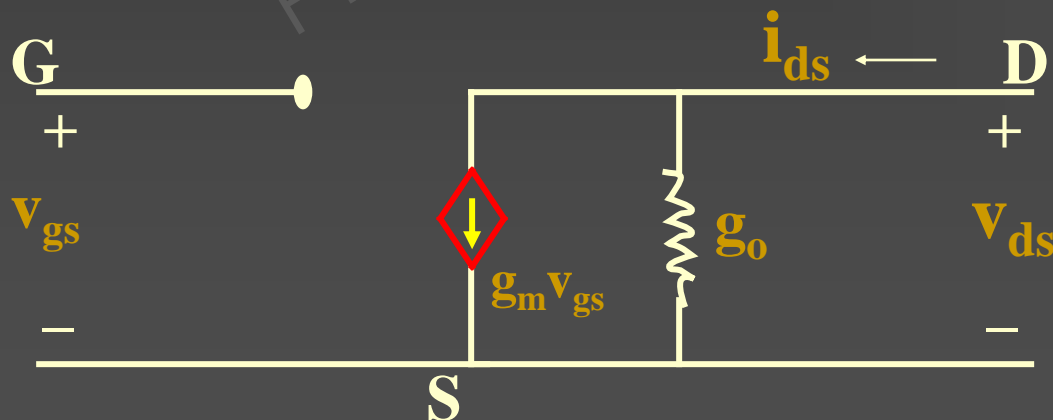
MOSFET y-parameter model

$$\mathbf{i}_{ds} = y_{21}\mathbf{V}_{gs} + y_{22}\mathbf{V}_{ds} \text{ ————— (2)}$$

Substituting the values for y_{21} and y_{22} ,

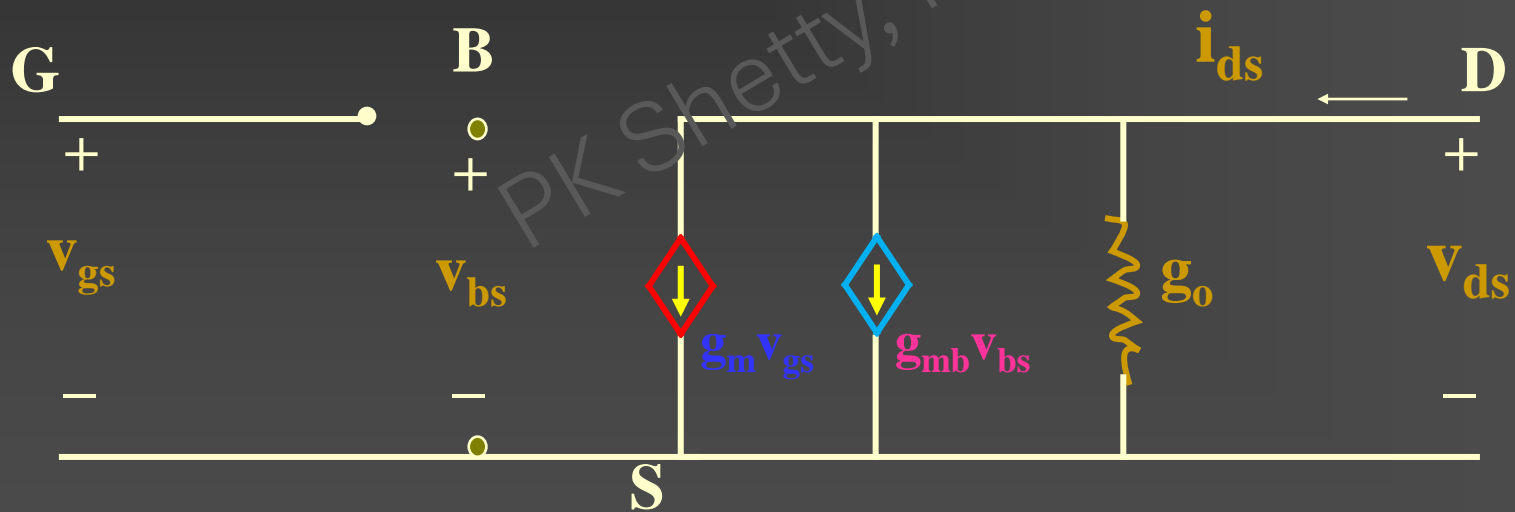
$$\mathbf{i}_{ds} = g_m\mathbf{V}_{gs} + g_o\mathbf{V}_{ds}$$

\therefore MOSFET model is,



Complete MOSFET model

If we consider the “*body effect*”, then the model requires another transconductance generator source, $g_{mb}V_{bs}$.

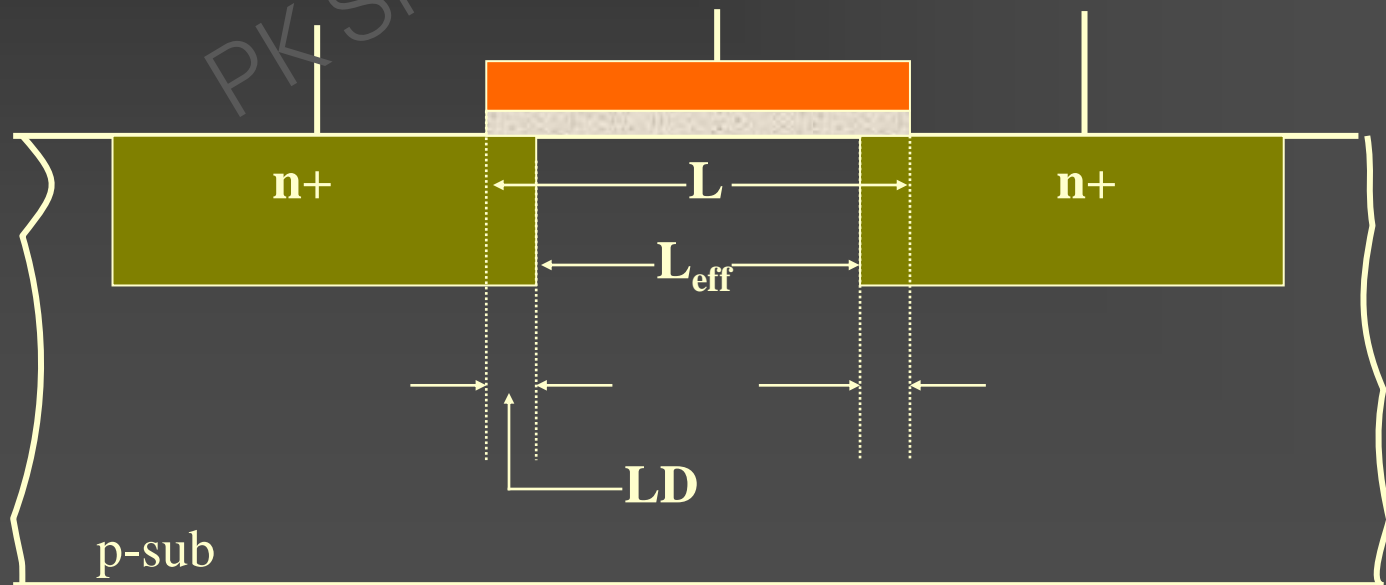


High Frequency MOSFET model

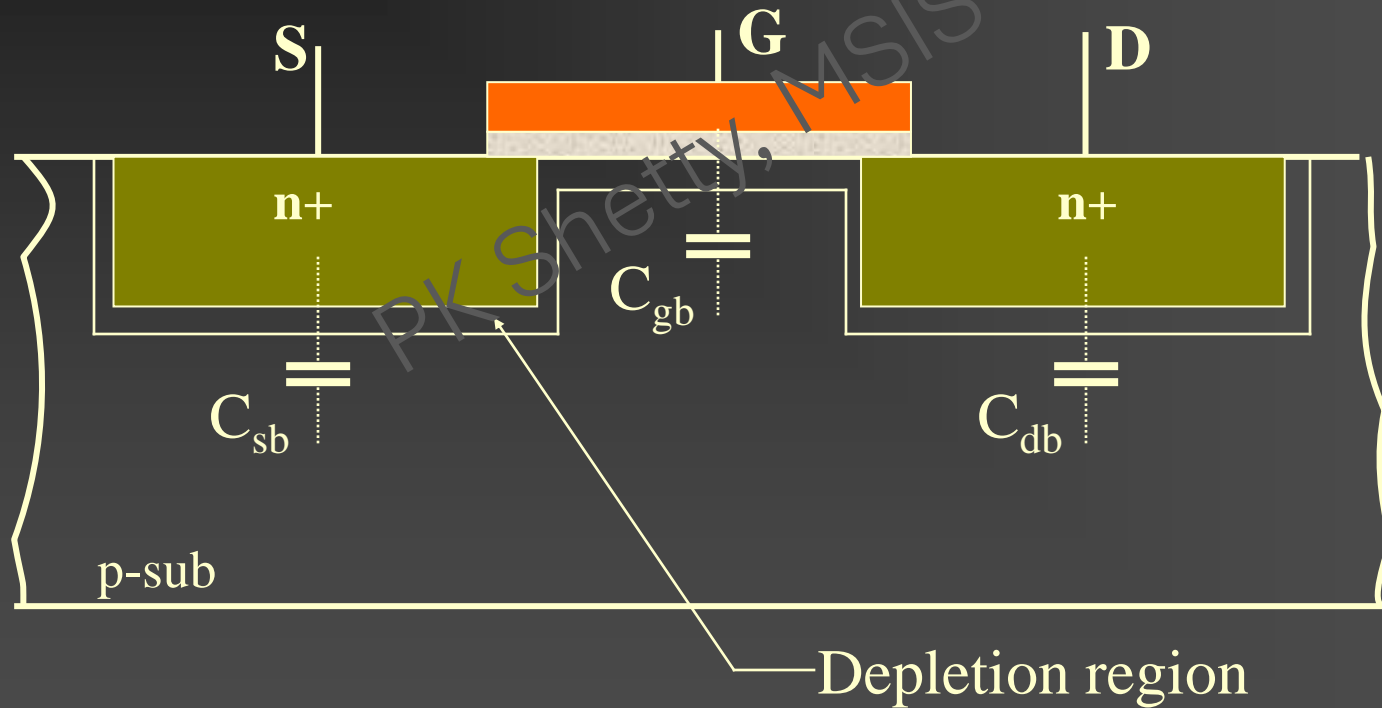
H. F. model = L. F. model + MOSFET capacitances.

$$L_{\text{eff}} = (L - 2LD)$$

Capacitances introduced: C_{gs} and C_{gd}

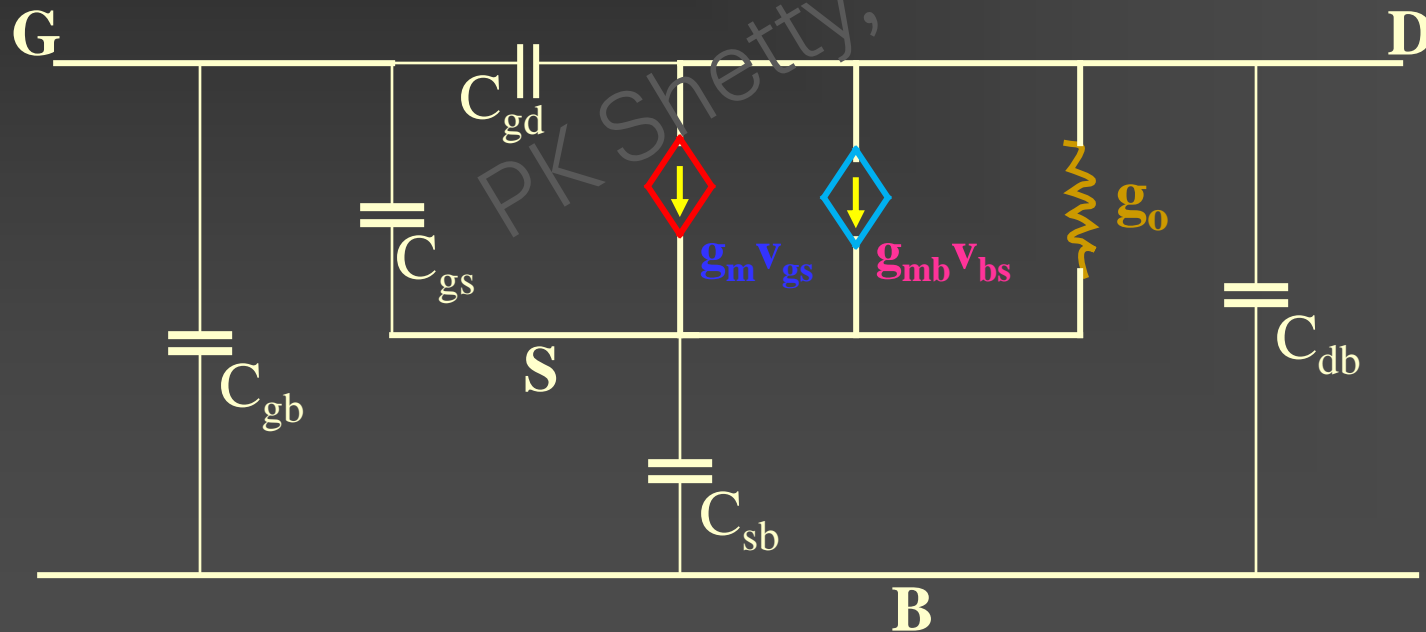


High Frequency MOSFET model



High Frequency MOSFET model

Adding these 5 capacitances to the L. F. MOSFET model:



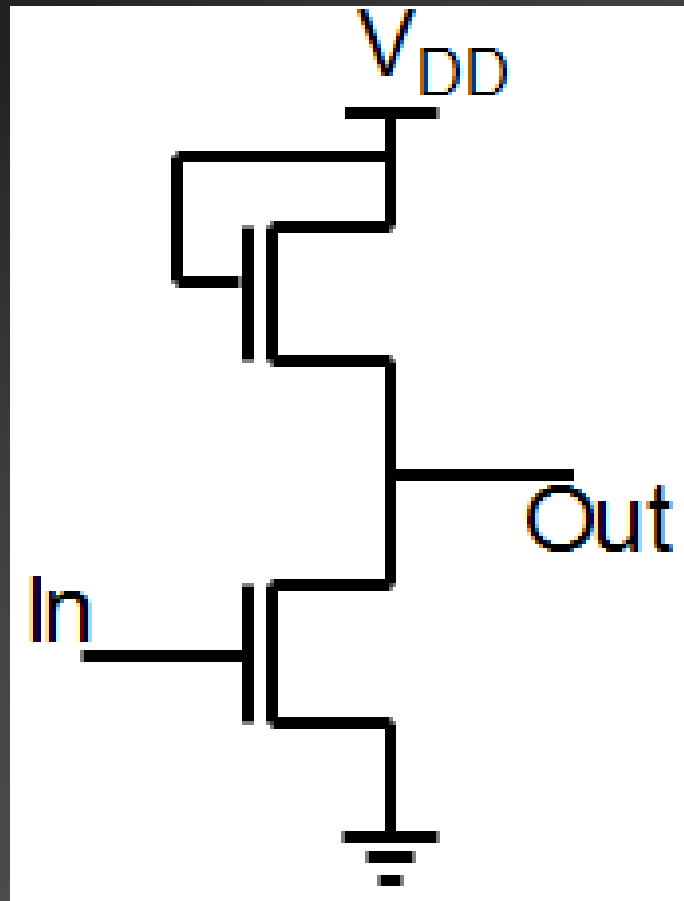
Capacitance Estimation

1. $C_{gb} = \epsilon_{ox}(L-2LD)W/t_{ox} = C_{ox}(L_{eff})W$
2. $C_{gd} = \epsilon_{ox}(LD)W/t_{ox} = C_{ox}(LD) W = CGDO. W$
3. $C_{gs} = \epsilon_{ox}(LD)W/t_{ox} = C_{ox}(LD) W = CGSO. W$
4. $C_{sb} = C_{sb,bottom} + C_{sb,sidewall}$
5. $C_{db} = C_{db,bottom} + C_{db,sidewall}$

where, $C_{s(d)b,bottom} = \frac{CJ.AS(D)}{(1+V_{DB}/PB)^{MJ}}$

$$C_{s(d)b,sidewall} = \frac{CJSW.PS(D)}{(1+V_{DB}/PBSW)^{MJSW}}$$

Draw the small signal model for the circuit shown below:



MOSFET Model

$$I_{DS} = \frac{1}{2} K_n W/L (V_{GS} - V_{TH})^2 (1 + \lambda V_{DS})$$

SPICE Models

Used to simulate CMOS ICs. These MOSFET models provide a description of how a transistor will behave in the designed circuit. Thus, the models serve as the connection between the designed circuit and the underlying fabrication technology.

- SPICE model Level1, Level2, Level3
- BSIM (**B**erkeley **S**hort-Channel **I**GFET **M**odel)

Eg.:- BSIM1, BSIM2, BSIM3,

BSIM4.0.0 (released on 24.03.2000),

BSIM4.4.0 (released on 04.03.2004),

BSIM Model

- At one time, nearly every company developed its own compact models
- In 1996, the Compact Model Council, an industry standard setting group sponsored by most of the world's largest semiconductor manufacturers and design tool companies, set out to select one standard model
- It selected **BSIM** as the world's first industry standard model in 1997
- Now, nearly all the semiconductor companies in the world use BSIM to some degree.
- If the I_{ds} equation of BSIM is typed out on paper, it will fill two pages.

SPICE MODEL PARAMETERS OF MOSFETS

LEVEL	Model type (1, 2, or 3)
L	Channel length
W	Channel width
LD	Lateral diffusion length
WD	Lateral diffusion width
VTO	Zero-bias threshold voltage
KP	Transconductance
GAMMA	Bulk threshold parameter
PHI	Surface potential
LAMBDA	Channel-length modulation
CJ	Bulk p-n zero-bias bottom capacitance/length
CJSW	Bulk p-n zero-bias perimeter capacitance/length
MJ	Bulk p-n bottom grading coefficient